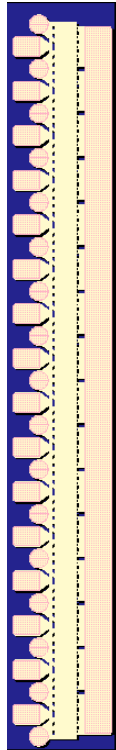


100 Watt Discrete Power GaN on SiC HEMT



Key Features

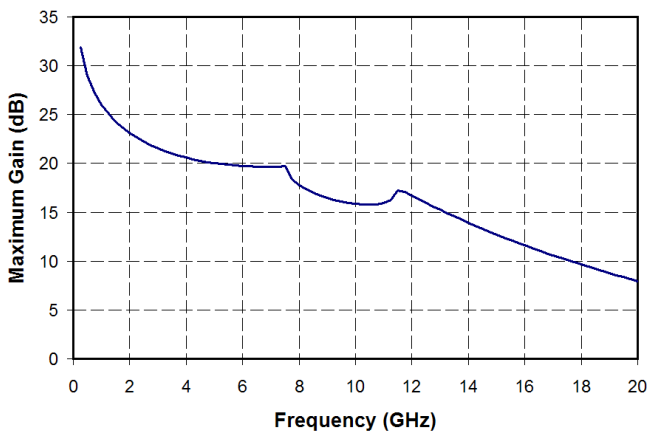
- Frequency Range: DC - 18 GHz
- > 50 dBm Nominal Psat
- 55% Maximum PAE
- 15 dB Nominal Power Gain
- Bias: Vd = 28 - 40 V, Idq = 2 A, Vg = -3 V Typical
- Technology: 0.25 um Power GaN on SiC
- Chip Dimensions: 0.82 x 4.56 x 0.10 mm

Primary Applications

- Space
- Military
- Broadband Wireless

Measured Performance

Bias conditions: Vd = 28 - 40 V, Idq = 2 A, Vg = -3 V Typical



Product Description

The TriQuint TGF2023-20 is a discrete 20 mm GaN on SiC HEMT which operates from DC-18 GHz. The TGF2023-20 is designed using TriQuint's proven 0.25um GaN production process. This process features advanced field plate techniques to optimize microwave power and efficiency at high drain bias operating conditions.

The TGF2023-20 typically provides > 50 dBm of saturated output power with power gain of 15 dB. The maximum power added efficiency is 55% which makes the TGF2023-20 appropriate for high efficiency applications.

Lead-free and RoHS compliant

Datasheet subject to change without notice.

Table I
Absolute Maximum Ratings 1/

| Symbol | Parameter | Value | Notes |
|---------------|-----------------------------|--------------|--------------|
| Vd | Drain Voltage | 40 V | <u>2/</u> |
| Vg | Gate Voltage Range | -10 to 0 V | |
| Id | Drain Current | 20 A | <u>2/</u> |
| Ig | Gate Current | 112 mA | |
| Pin | Input Continuous Wave Power | 38 dBm | <u>2/</u> |

- 1/ These ratings represent the maximum operable values for this device. Stresses beyond those listed under “Absolute Maximum Ratings” may cause permanent damage to the device and / or affect device lifetime. These are stress ratings only, and functional operation of the device at these conditions is not implied.
- 2/ Combinations of supply voltage, supply current, input power, and output power shall not exceed the maximum power dissipation listed in Table IV.

Table II
Recommended Operating Conditions

| Symbol | Parameter | Value |
|---------------|------------------------------|--------------|
| Vd | Drain Voltage | 28 - 40 V |
| Idq | Drain Current | 2 A |
| Id_Drive | Drain Current under RF Drive | 6 A |
| Vg | Gate Voltage | -3 V |

Table III
RF Characterization Table 1/
Bias: Vd = 32 V & 40 V, Idq = 2 A, Vg = - 3V Typical

| SYMBOL | PARAMETER | Vd = 40 V | Vd = 32 V | UNITS |
|--------------------------|-----------------------------|--------------|--------------|-------|
| Power Tuned: | | | | |
| P _{sat} | Saturated Output Power | 50.5 | 49.5 | dBm |
| PAE | Power Added Efficiency | 46 | 47 | % |
| Gain | Power Gain | 15 | 15 | dB |
| R _p <u>2/</u> | Parallel Resistance | 87.79 | 68.58 | Ω·mm |
| C _p <u>2/</u> | Parallel Capacitance | 0.444 | 0.461 | pF/mm |
| Γ _L <u>3/</u> | Load Reflection Coefficient | 0.905 ∠175.4 | 0.912 ∠176.3 | - |
| Efficiency Tuned: | | | | |
| P _{sat} | Saturated Output Power | 48 | 47.5 | dBm |
| PAE | Power Added Efficiency | 55 | 57 | % |
| Gain | Power Gain | 19.5 | 19.5 | dB |
| R _p <u>2/</u> | Parallel Resistance | 190.2 | 158.1 | Ω·mm |
| C _p <u>2/</u> | Parallel Capacitance | 0.263 | 0.314 | pF/mm |
| Γ _L <u>3/</u> | Load Reflection Coefficient | 0.843 ∠169.0 | 0.866 ∠170.9 | - |

1/ Values in this table are scaled from a 1.25 mm unit GaN on SiC cell at 3.5 GHz

2/ Large signal equivalent GaN on SiC output network

3/ Optimum load impedance for maximum power or maximum PAE at 3.5 GHz. The series resistance and inductance (R_d and L_d) shown in the Figure on page 5 is excluded

Table IV
Power Dissipation and Thermal Properties 1/

| Parameter | Test Conditions | Value | Notes |
|---|--|--|--------------|
| Maximum Power Dissipation | Tbaseplate = 75 °C | Pd = 80 W Tchannel = 150 °C Tm = 2.0E+6 Hrs | <u>2/ 3/</u> |
| Thermal Resistance, θ_{jc} | Vd = 40 V Id = 2 A Pd = 80 W Tbaseplate = 75 °C | $\theta_{jc} = 1.0$ (°C/W) Tchannel = 150 °C Tm = 2.0E+6 Hrs | |
| Thermal Resistance, θ_{jc} Under RF Drive | Vd = 40 V Id = 6 A Pout = 50.5 dBm Pd = 127.8 W Tbaseplate = 22 °C | $\theta_{jc} = 1.0$ (°C/W) Tchannel = 150 °C Tm = 2.0E+6 Hrs | <u>4/</u> |
| Mounting Temperature | 30 Seconds | 320 °C | |
| Storage Temperature | | -65 to 150 °C | |

1/ Assumes eutectic attach using 1mil thick 80/20 AuSn mounted to a 10mil CuMo Carrier Plate

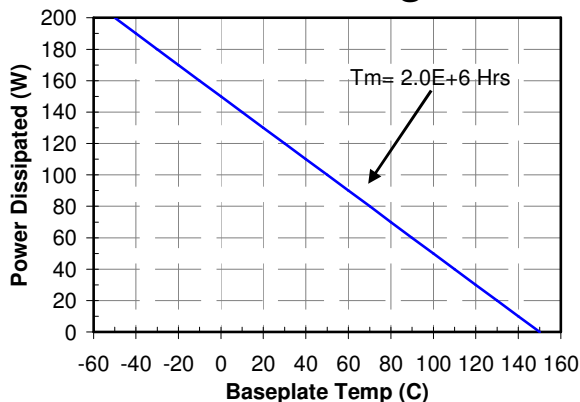
2/ For a median life of 2E+6 hours, Power Dissipation is limited to

$$Pd(max) = (150 \text{ °C} - Tbase \text{ °C})/\theta_{jc}.$$

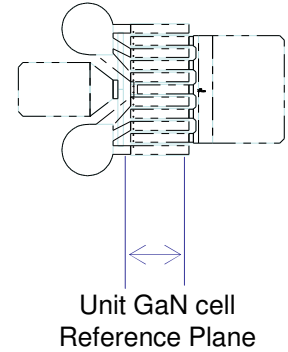
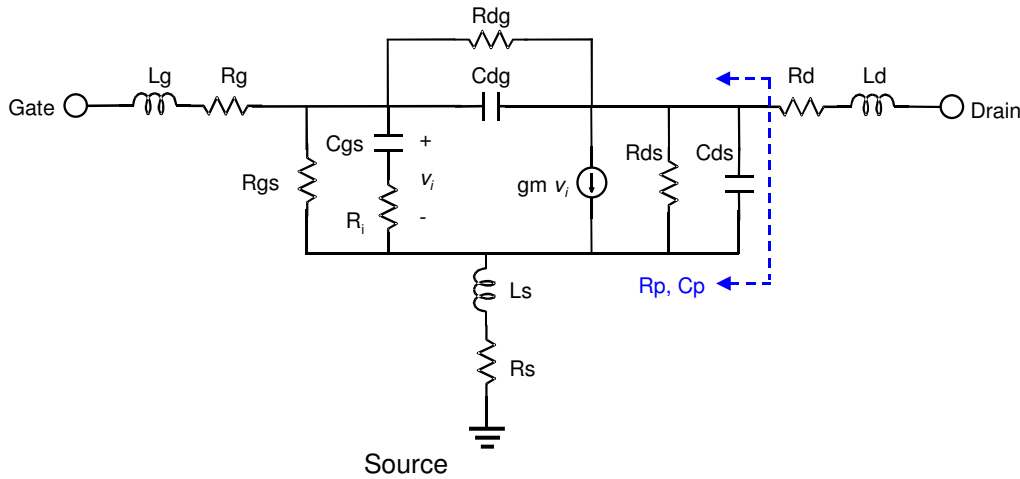
3/ Channel operating temperature will directly affect the device median time to failure (MTTF). For maximum life, it is recommended that channel temperatures be maintained at the lowest possible levels.

4/ Channel temperatures at high drain voltages can be excessive, leading to reduced MTTF. Operation at reduced baseplate temperatures and/or pulsed RF modulation is recommended.

Power De-rating Curve

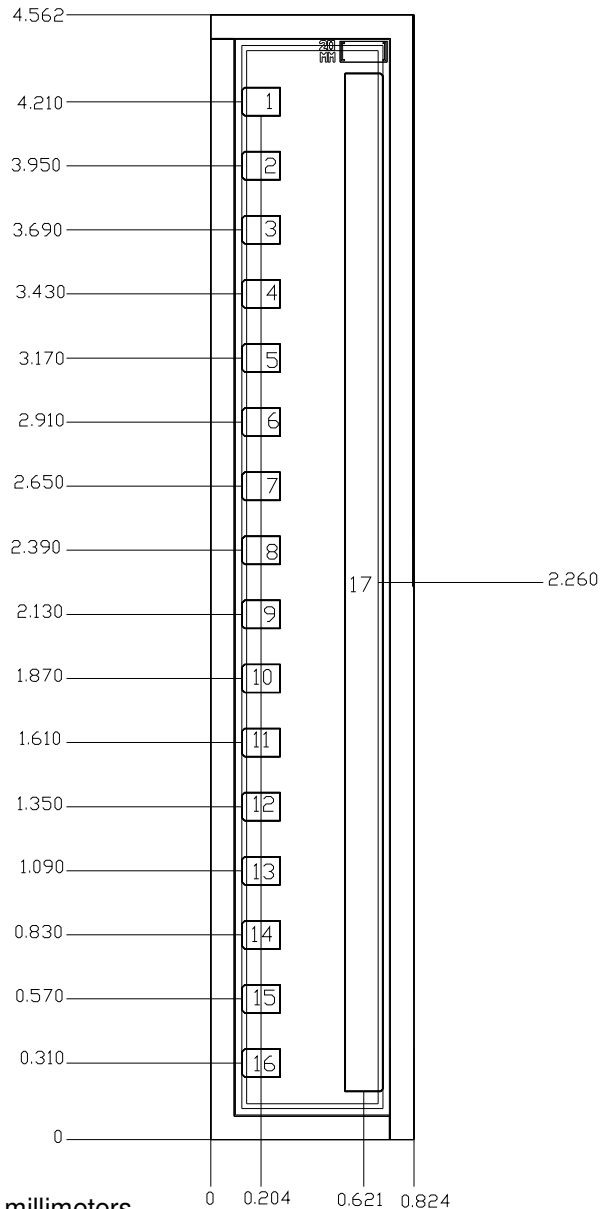


Linear Model for 1.25 mm Unit GaN Cell



| MODEL PARAMETER | Vd = 40V Idq = 19mA | Vd = 32V Idq = 19mA | UNITS |
|-----------------|------------------------|------------------------|-------|
| Rg | 0.56 | 0.56 | Ω |
| Rs | 0.08 | 0.07 | Ω |
| Rd | 0.31 | 0.33 | Ω |
| gm | 0.134 | 0.138 | S |
| Cgs | 1.52 | 1.50 | pF |
| Ri | 0.24 | 0.23 | Ω |
| Cds | 0.239 | 0.263 | pF |
| Rds | 373.7 | 319.2 | Ω |
| Cgd | 0.053 | 0.0646 | pF |
| Tau | 4.11 | 3.57 | pS |
| Ls | 0.0148 | 0.0147 | nH |
| Lg | -0.0135 | -0.013 | nH |
| Ld | 0.048 | 0.0485 | nH |
| Rgs | 1550 | 1950 | Ω |
| Rgd | 70500 | 47800 | Ω |

Mechanical Drawing



Units: millimeters

Thickness: 0.100

Die x,y size tolerance: +/- 0.050

Chip edge to bond pad dimensions are shown to center of pad

Ground is backside of die

| | | |
|------------------|----|---------------|
| Bond Pad #1 - 16 | Vg | 0.154 x 0.115 |
| Bond Pad #17 | Vd | 0.154 x 4.130 |

GaAs MMIC devices are susceptible to damage from Electrostatic Discharge. Proper precautions should be observed during handling, assembly and test.

Assembly Notes

Component placement and adhesive attachment assembly notes:

- Vacuum pencils and/or vacuum collets are the preferred method of pick up.
- Air bridges must be avoided during placement.
- The force impact is critical during auto placement.
- Organic attachment (i.e. epoxy) can be used in low-power applications.
- Curing should be done in a convection oven; proper exhaust is a safety concern.

Reflow process assembly notes:

- Use AuSn (80/20) solder and limit exposure to temperatures above 300°C to 3-4 minutes, maximum.
- An alloy station or conveyor furnace with reducing atmosphere should be used.
- Do not use any kind of flux.
- Coefficient of thermal expansion matching is critical for long-term reliability.
- Devices must be stored in a dry nitrogen atmosphere.

Interconnect process assembly notes:

- Ball bonding is the preferred interconnect technique, except where noted on the assembly diagram.
- Force, time, and ultrasonics are critical bonding parameters.
- Aluminum wire should not be used.
- Devices with small pad sizes should be bonded with 0.0007-inch wire.

Ordering Information

| Part | Package Style |
|------------|----------------|
| TGF2023-20 | GaN on SiC Die |

GaAs MMIC devices are susceptible to damage from Electrostatic Discharge. Proper precautions should be observed during handling, assembly and test.